

Notice of References Cited

Application/Control No.

10/054,847

Applicant(s)/Patent Under
Reexamination
RHODES, HOWARD E.

Examiner

Toniae M. Thomas

Art Unit

2822

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,118,142 B1	09-2000	CHEN et al.	257/232
	C	US-6,232,626 B1	05-2001	RHODES	257/292
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	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Ph.D., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films," Stanley, Richard Tauber, Ph.D., Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, pages 177-178.
	V	Wolf, Ph.D., "Aluminum Thin Films and Physical Vapor Deposition" Stanley, Richard Tauber, Ph.D., Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, page 335.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.